



January 22, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
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Subject: | Serial No. 10/714,305 11/14/03 |

Jei-Wei Chang et al.

SINGLE LAYER RESIST LIFTOFF PROCESS
FOR NANO TRACK WIDTH

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on January 27, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

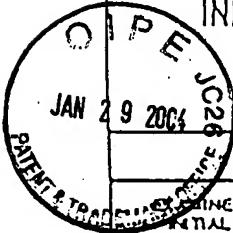
U.S. Patent 6,519,124 to Redon et al., "Magnetic Tunnel Junction Read Head Using a Hybrid, Low-Magnetization Flux Guide," discloses a conventional lift-off resist process.

U.S. Patent 5,212,044 to Liang et al., "Photoresist Composition Including Polyphenol and Sensitizer," describes a method of hardening a resist using an ion beam.

Sincerely,



Stephen B. Ackerman,
Reg. No. 37761



Form PTO-1449

**INFORMATION DISCLOSURE CITATION
IN AN APPLICATION**

(Use several sheets if necessary)

Doctor Number (Optional)

HTIRC-03-005

Afton Inn

10/714,305

Jei-Wei Chang et al.

Editorial

11/14/03

Filing Date

11/14/03

Group Action

U. S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS (including Author, Title, Date, Portion/Pages, Etc.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.